SPUTTERING TARGET

ABSTRACT

There are provided a sputtering target that can be efficiently produced, has excellent toughness, and can contribute to magnetic properties of a thin film; and an alloy suitable for the sputtering target. The alloy includes 50 at% or more and 70 at% or less of B, and one or two selected from the group consisting of Co and Fe. The alloy has a metallic structure with a crystal grain size of 30 μm or less. The metallic structure includes, as a matrix, a CoB phase, an FeB phase, or a CoFeB phase and a plurality of B phases dispersed in the matrix, and each B phase has an equivalent circular diameter of 30 μm or less.

(No Suitable Figure)